

Title: BATH AND METHOD FOR HIGH RATE COPPER

DEPOSITION

Inventors: B. Kim et al.

Docket No.: SEMT119849

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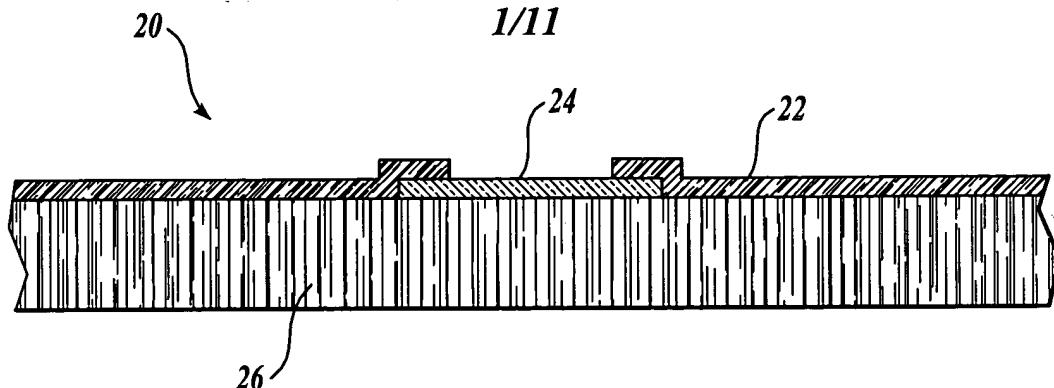


Fig. 1.

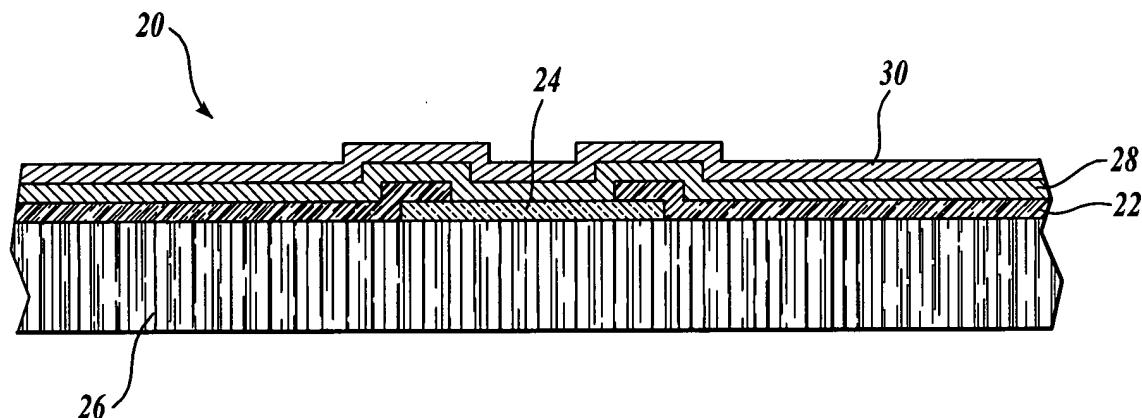


Fig. 2.

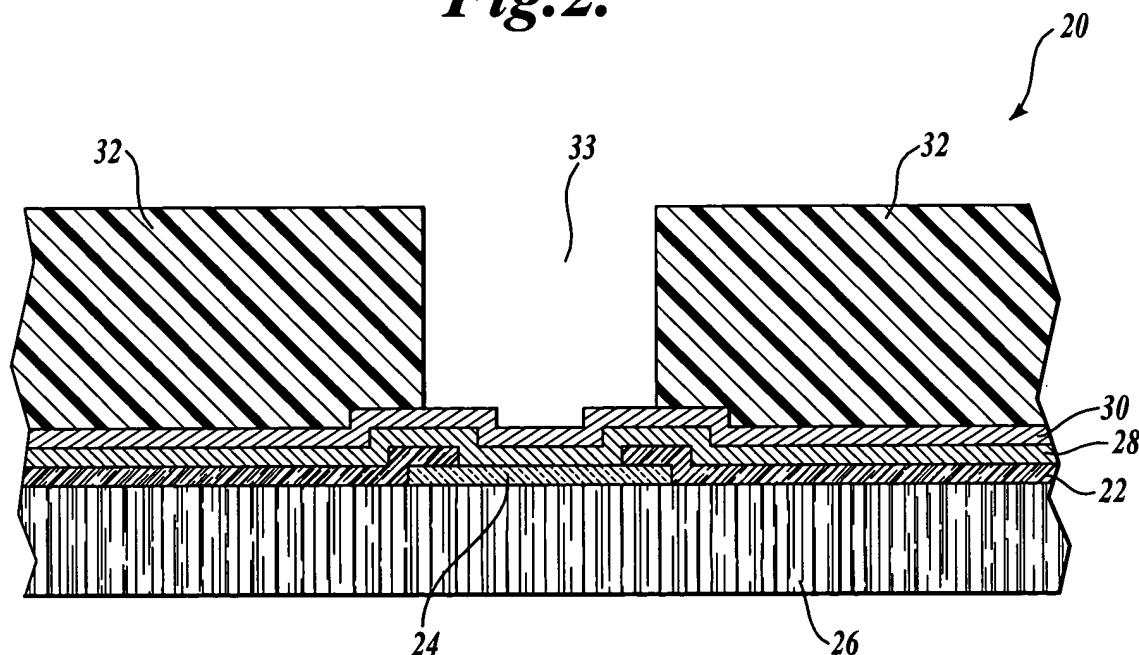


Fig. 3.

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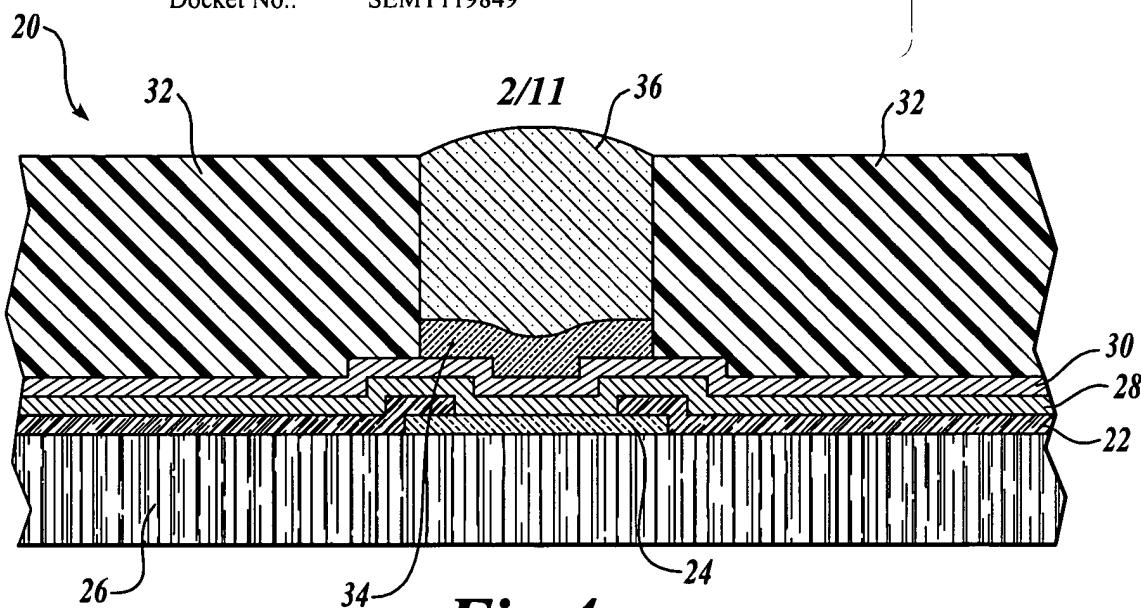


Fig. 4.

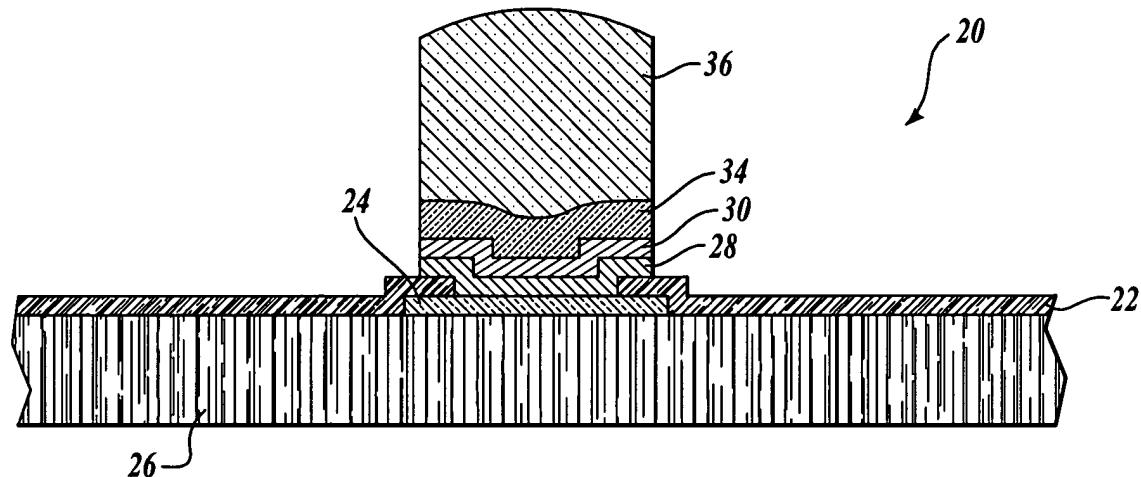


Fig. 5.

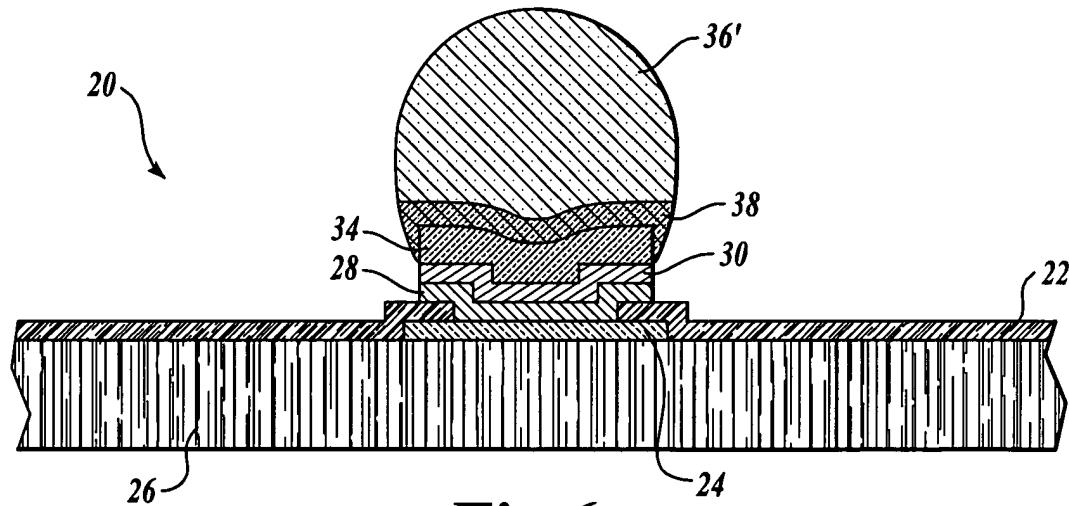


Fig. 6.

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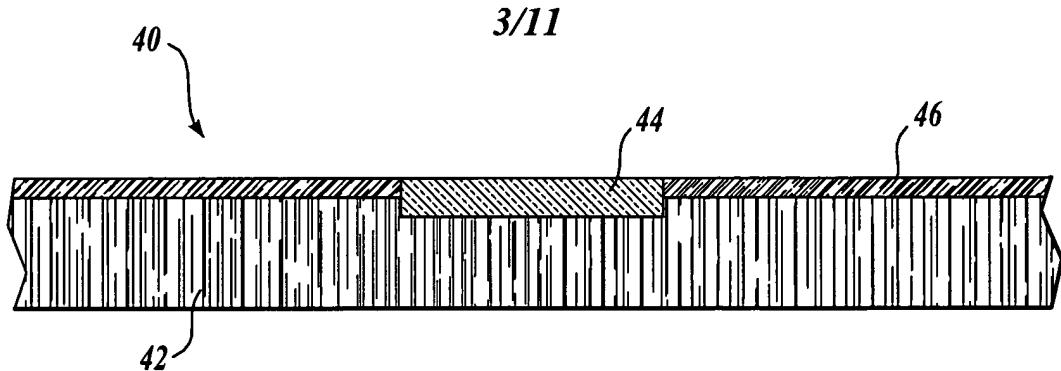


Fig. 7.

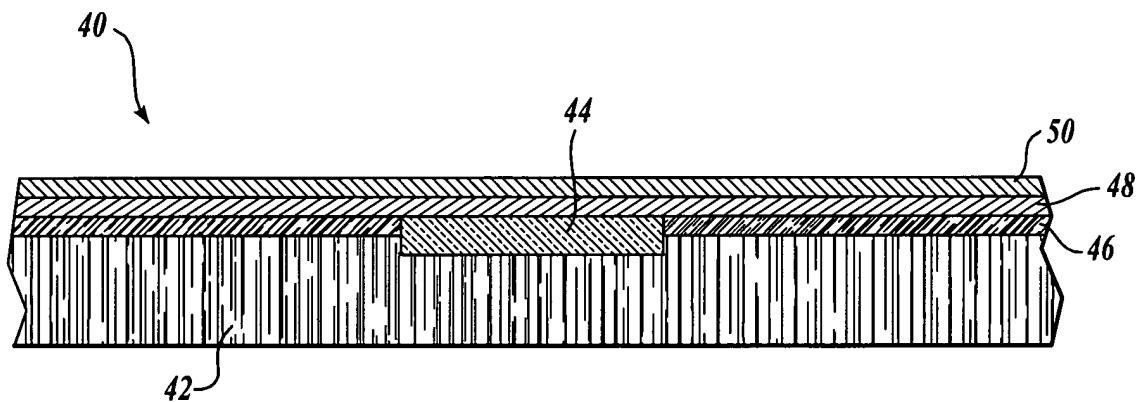


Fig. 8.

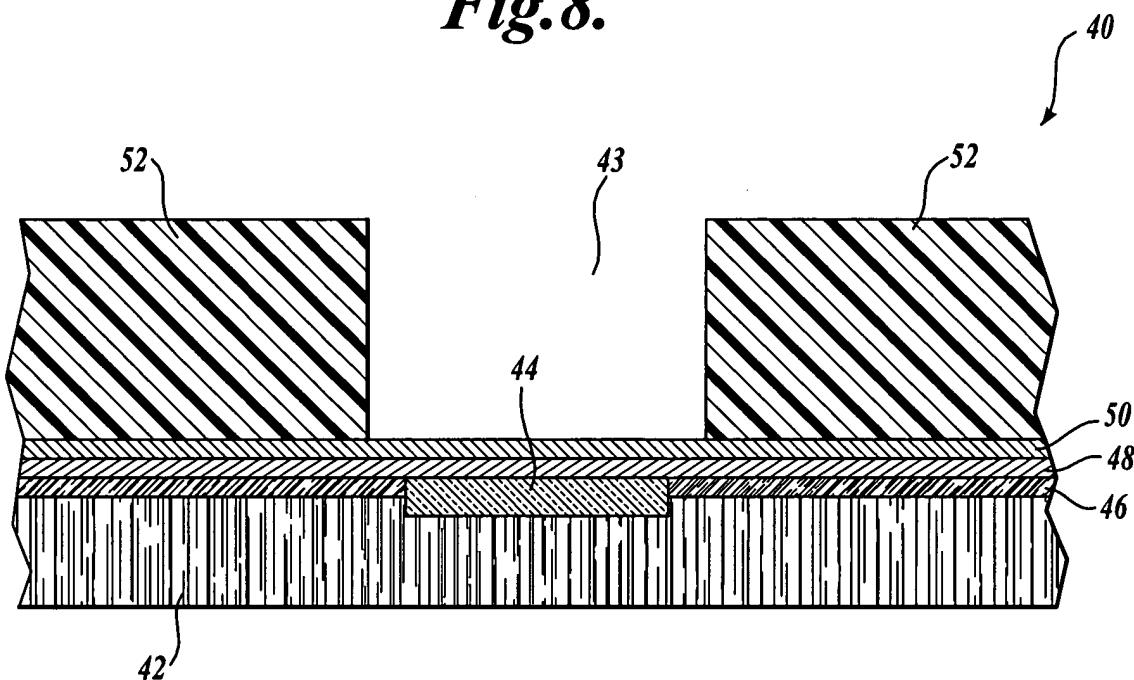


Fig. 9.

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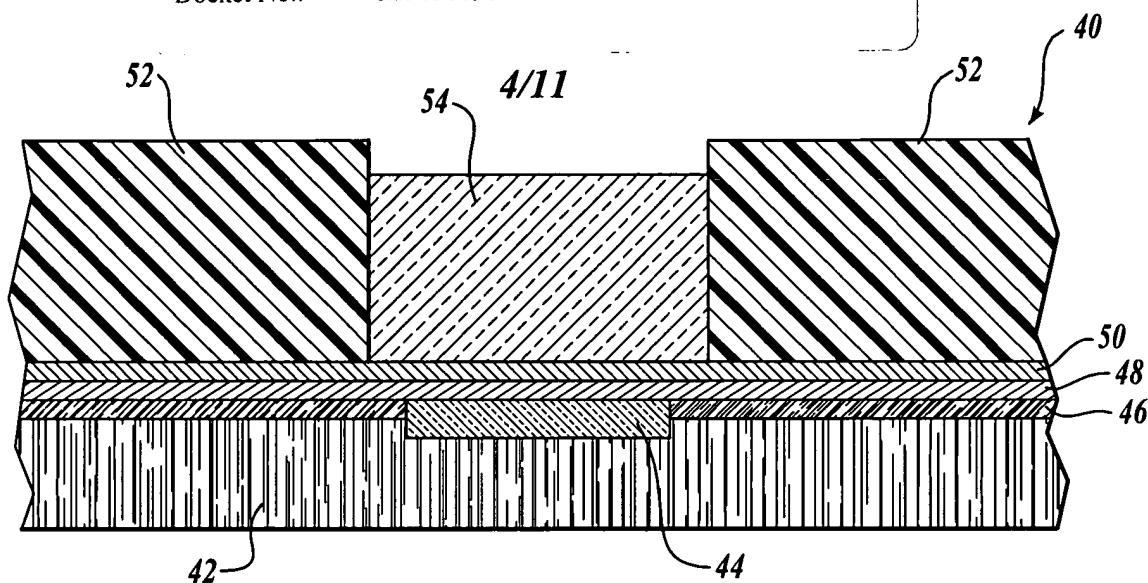


Fig.10.

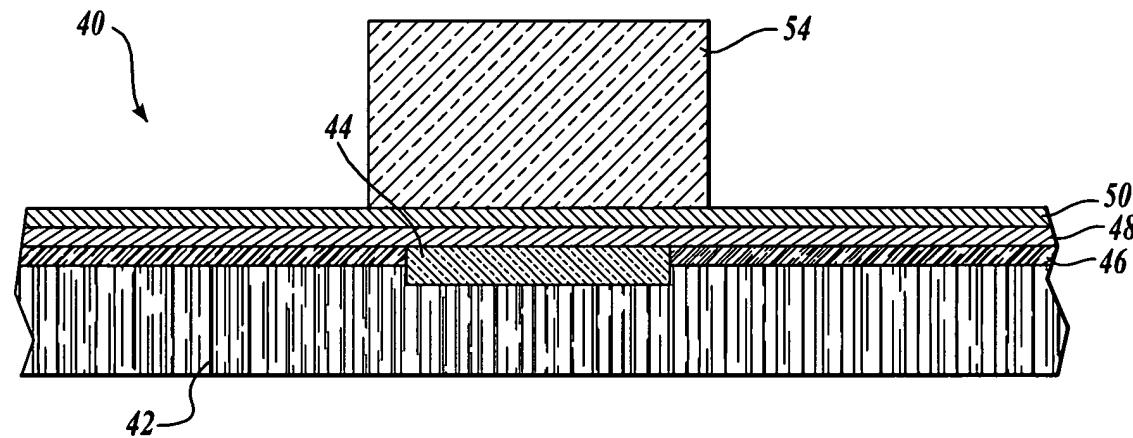


Fig.11.

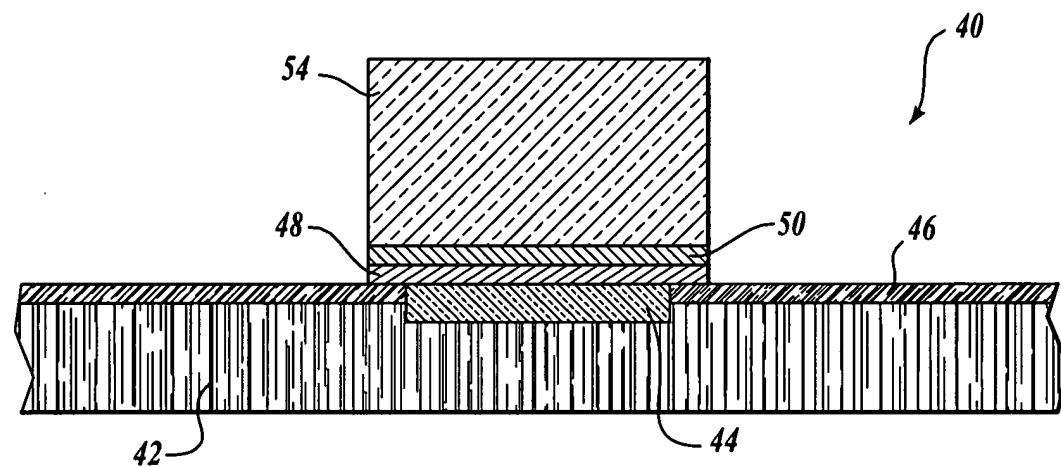


Fig.12.

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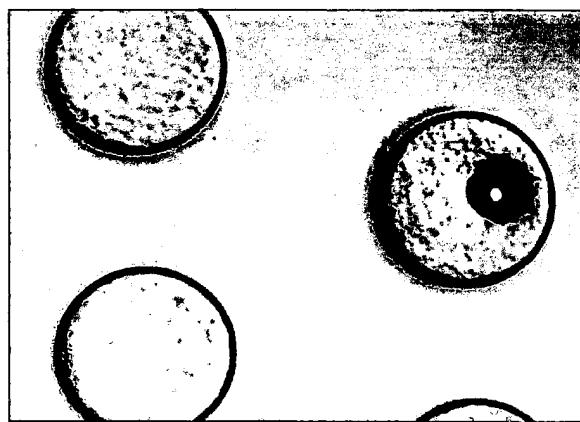


Fig.13.

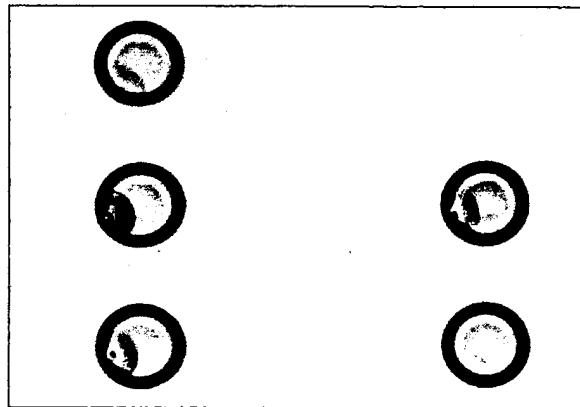


Fig.14.

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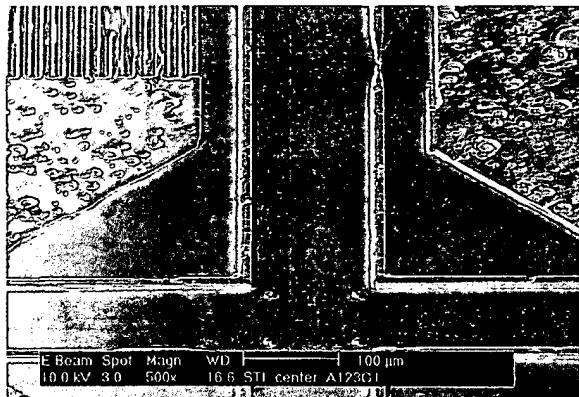


Fig.15.



Fig.16.

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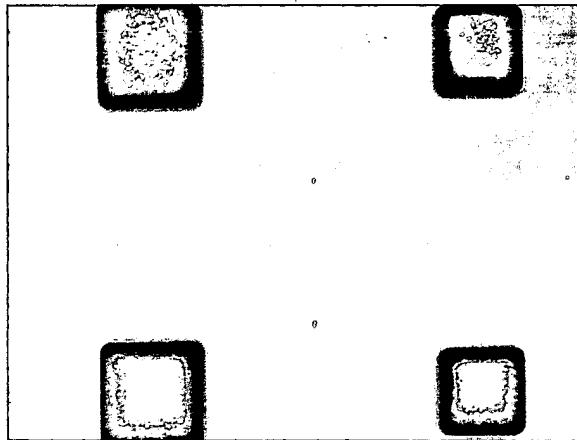


Fig.17.

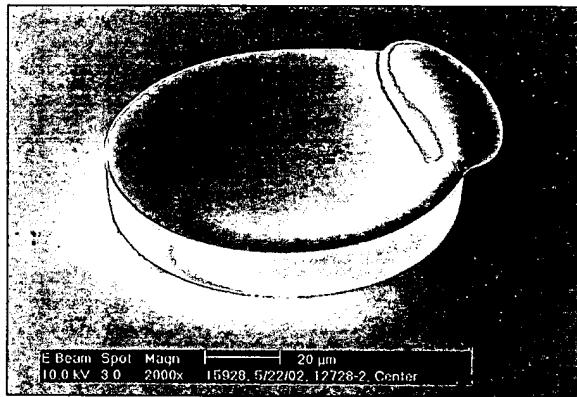


Fig.18.

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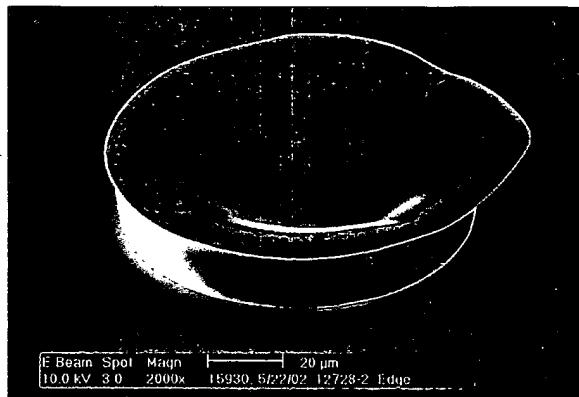


Fig.19.

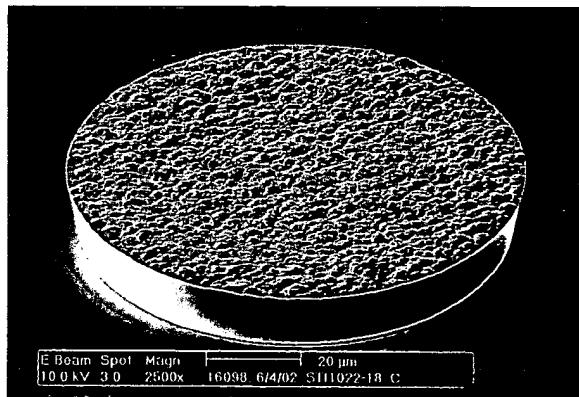


Fig.20.

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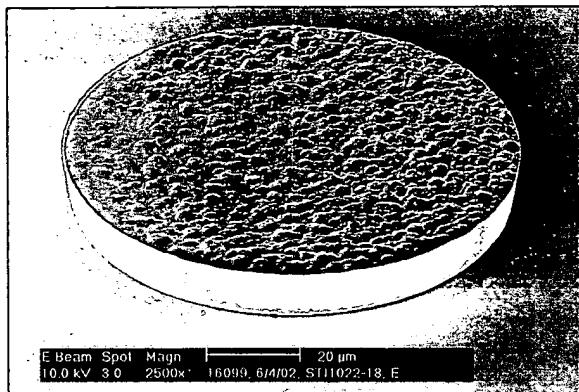


Fig.21.

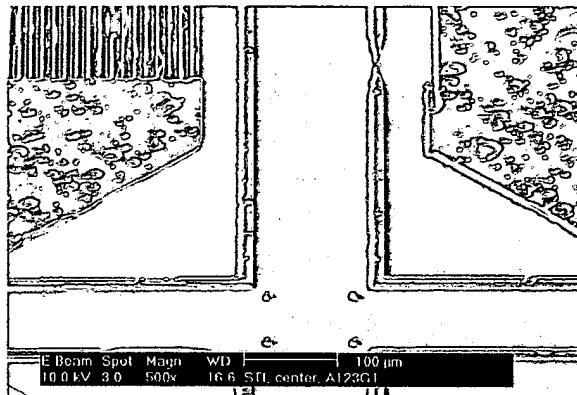


Fig.22.

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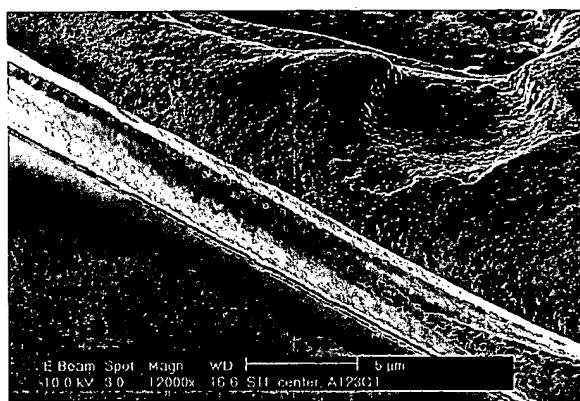


Fig.23.

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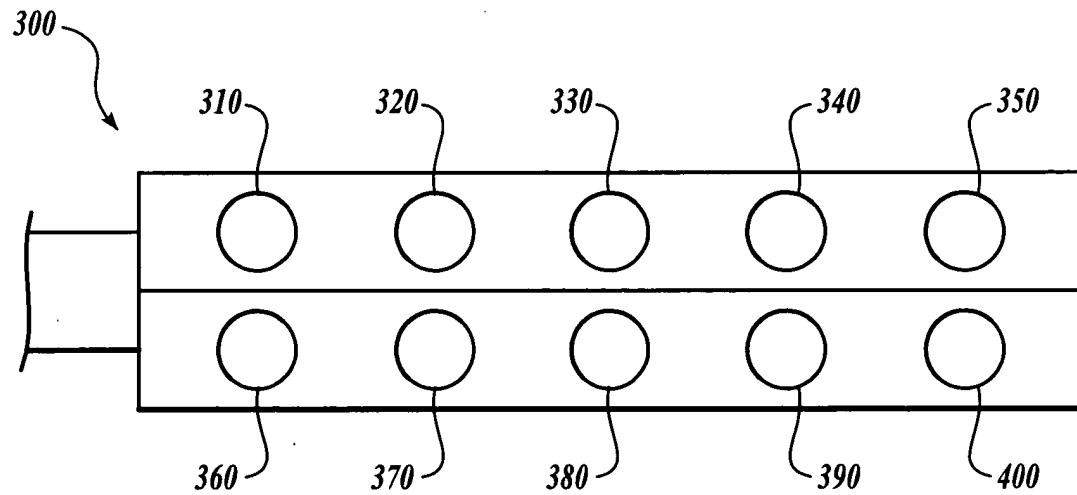


Fig.24.

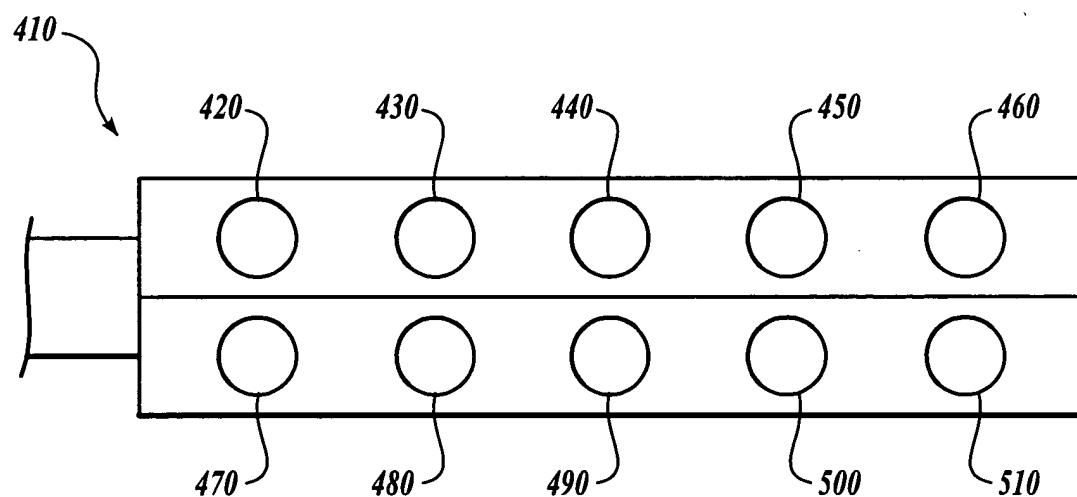


Fig.25.